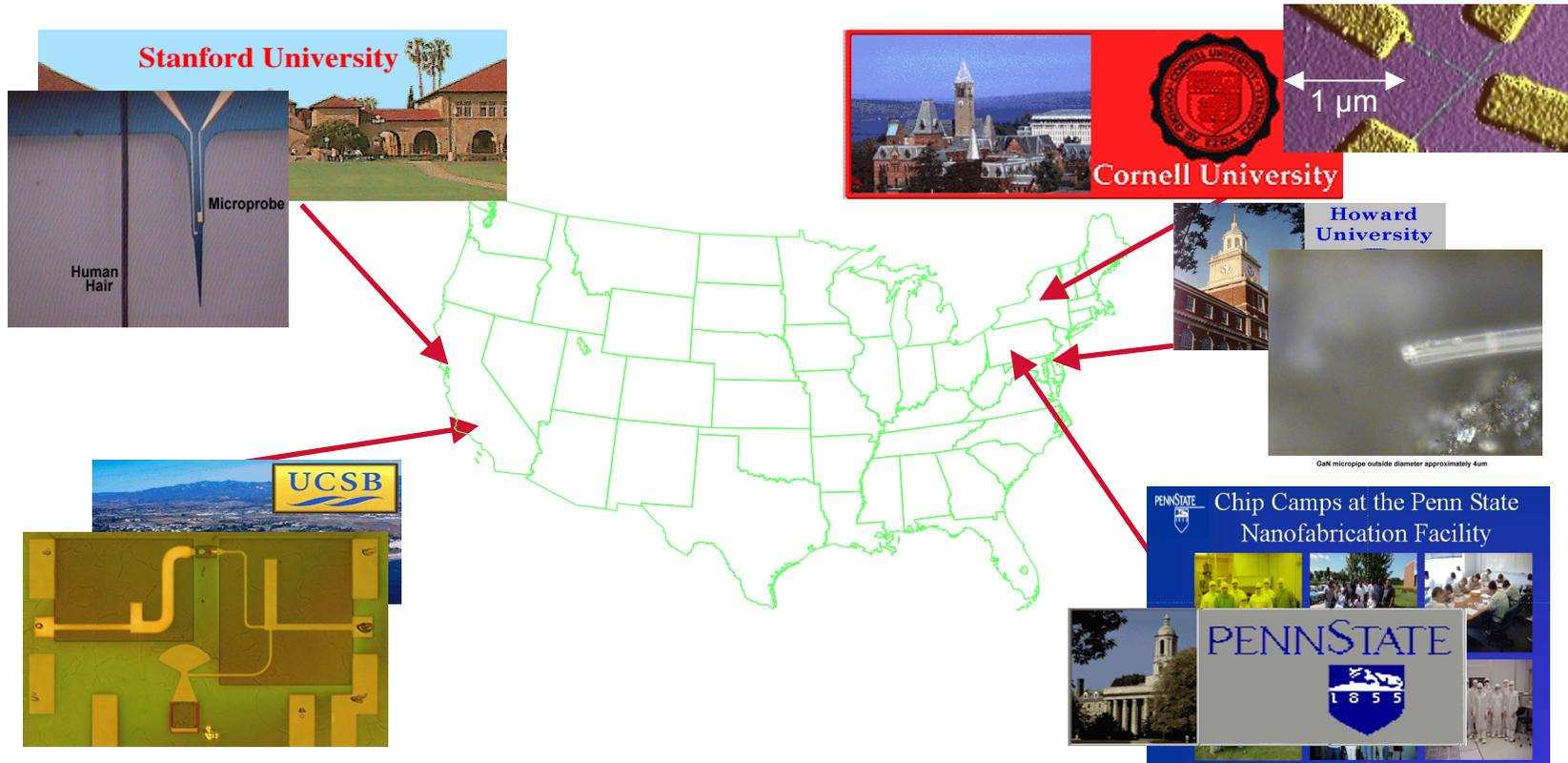


The National Nanofabrication Users Network



Sandip Tiwari

April 30, 2002

Page Overview- 1

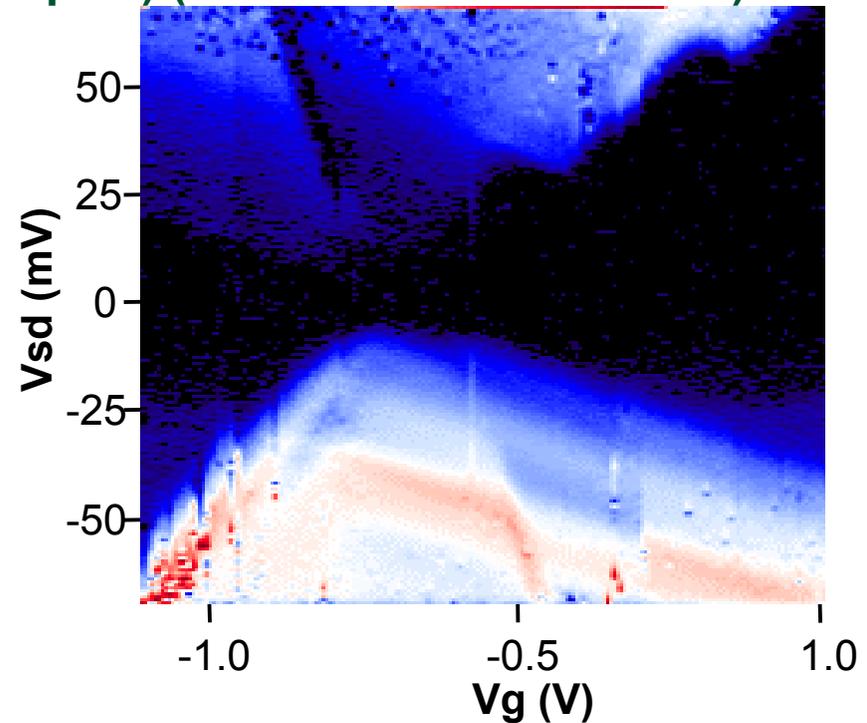
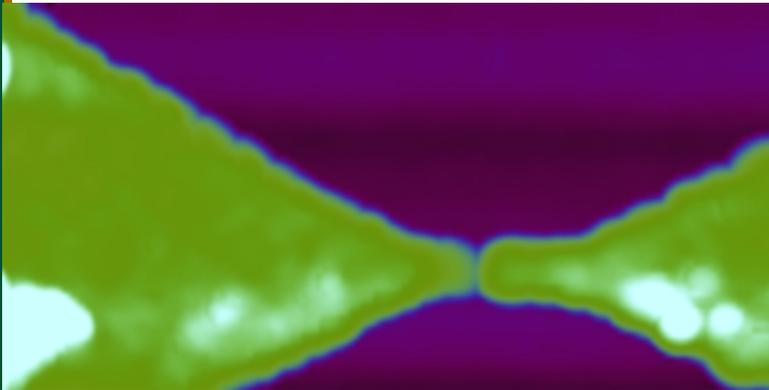
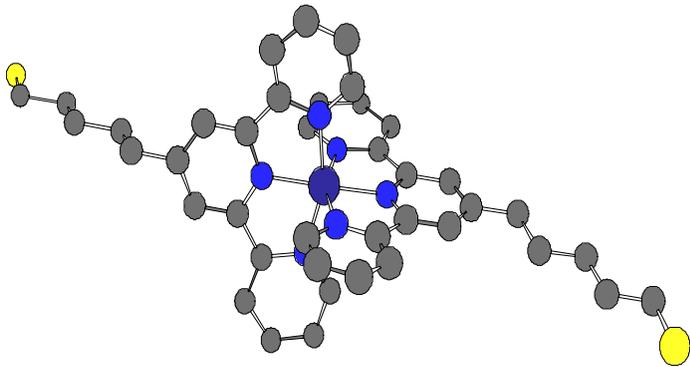


NNUN National Nanofabrication Users Network

Single-Electron Effects in Molecules

McEuen, Ralph, Abruna et al. (Cornell)

- two 4'-(5-Mercaptopentyl)-2,2':6',2''-terpyridinyl thiol (or tpy-SH) with Co atom (bis-tpySH Co complex) (octahedral coordination)



First observation of atomic phenomena
using direct electron transport
measurements

Page Overview- 2

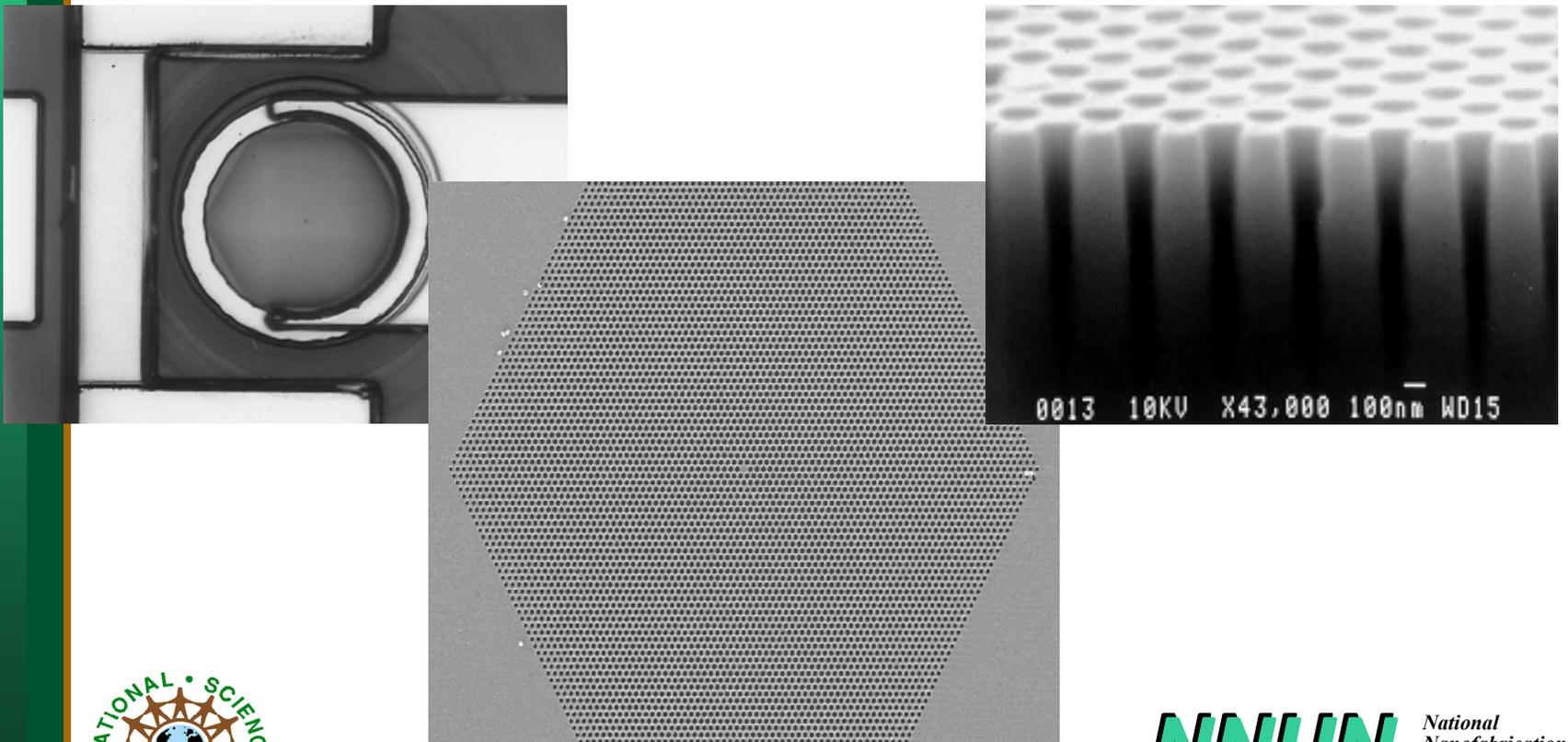
dl/dV (nS)
NNUN

National
Nanofabrication
Users Network

Photonic Crystal Microcavity Devices

P. Bhattacharya (U. Michigan)

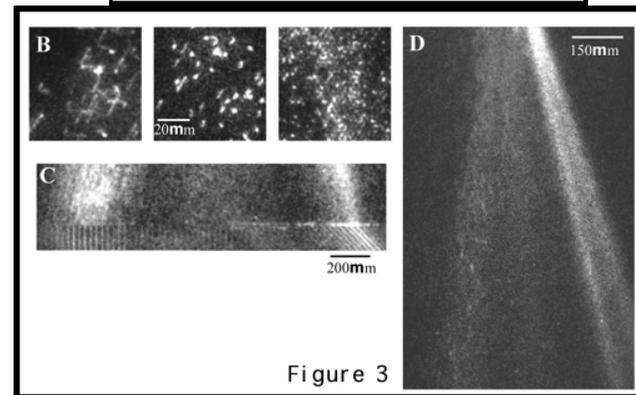
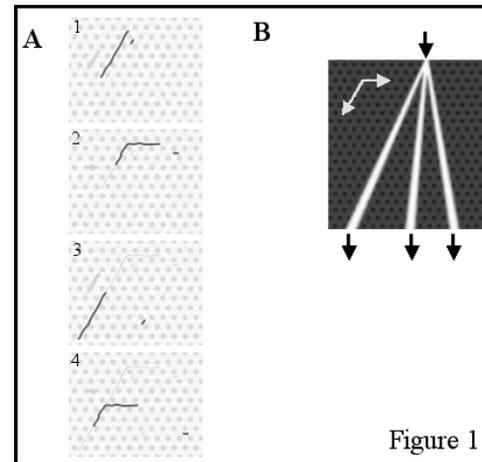
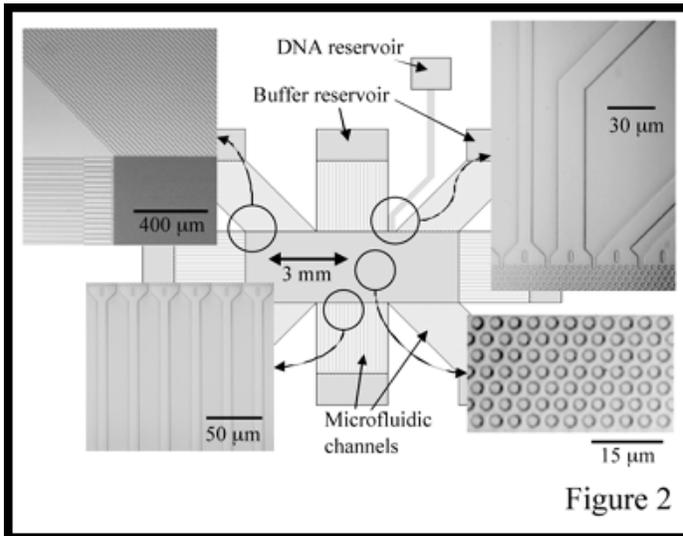
- VCSEL Lasers in InP-based system with oxide confinement using photonic crystal microcavity



DNA Prism: Continuous Fractionation of Genomic DNA

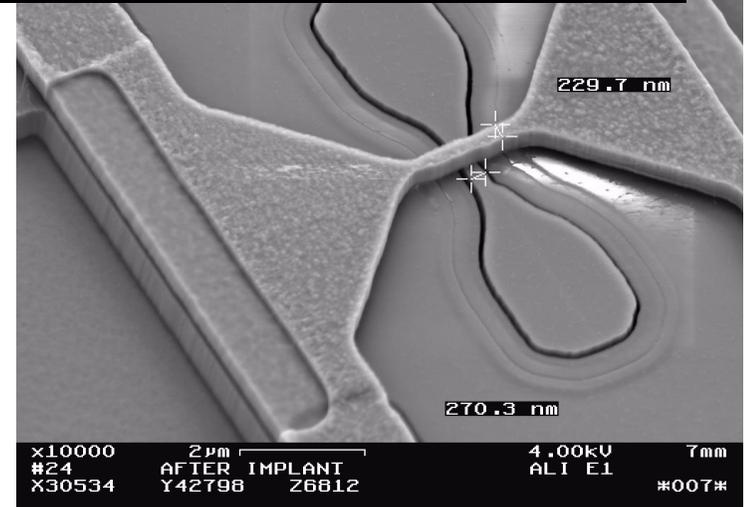
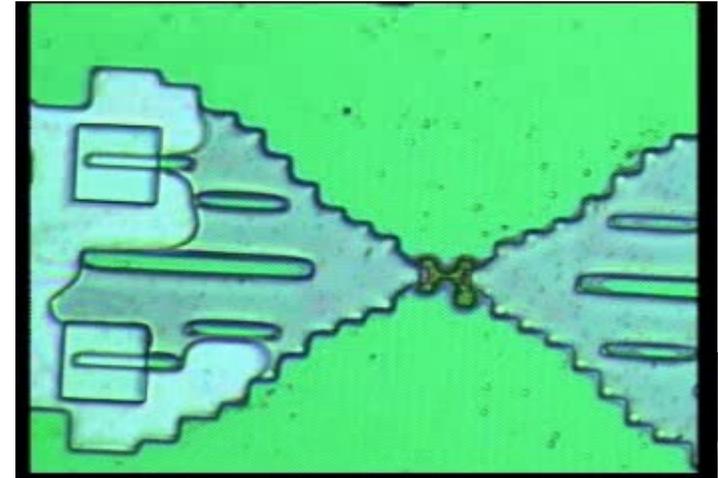
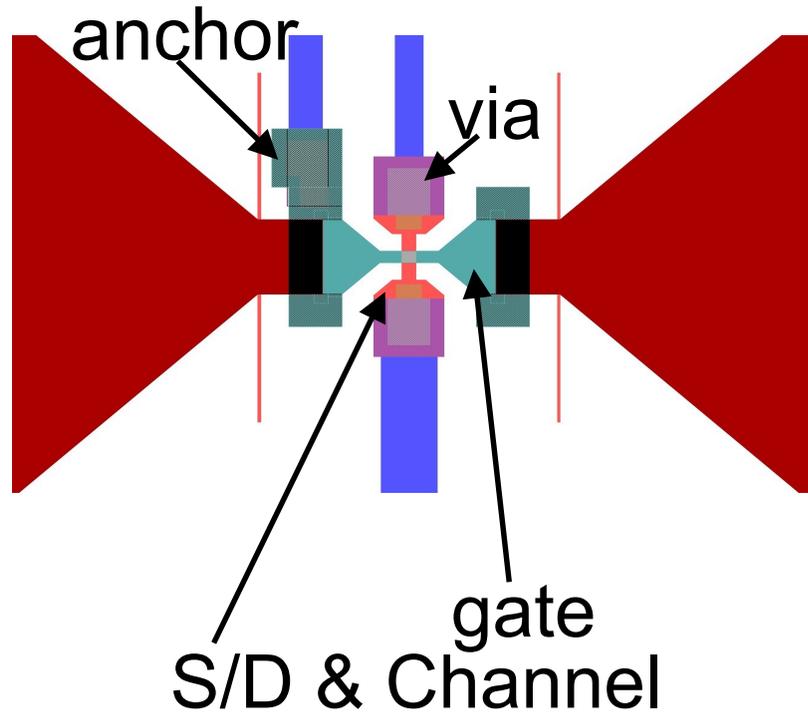
R. Austin (Princeton)

- Pulsed electrophoresis in a hexagonal array with alternating-angle electric field



Single Charge Sensing in Fluidics

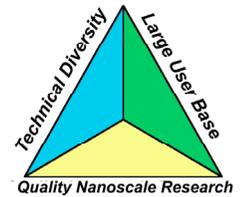
S. Tiwari (Cornell)



- First direct active gain assisted sequencing



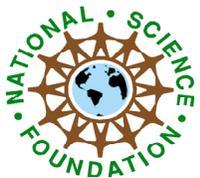
NNUN: Network Mission



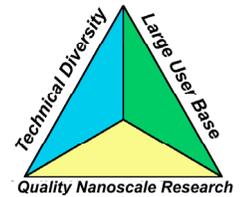
The challenge for nanotechnology:

How can the interdisciplinary science and engineering in this vast areas of industrial and economic significance, with its strong research content, high experimentation cost, and broad knowledge needs, be accomplished with broad participation?

- **Provide the nation's researchers with effective and efficient access to advanced nanofabrication equipment and expertise to enable top-quality research in nanotechnology across all disciplines**
- **Expand the applications of nanotechnology**
- **Broad spectrum of activities to support development of the scientists, engineers, and the work-force of future**



NNUN: Network Strategy



■ Effective research resource

- Networked partnership of state-of-art facilities with common and complementary infrastructure leveraging large user base
- Training and open access
- Expertise and support for simple and complex integrated experiments
- Focus on user needs, ease of use, and access

■ Applications of nanotechnology

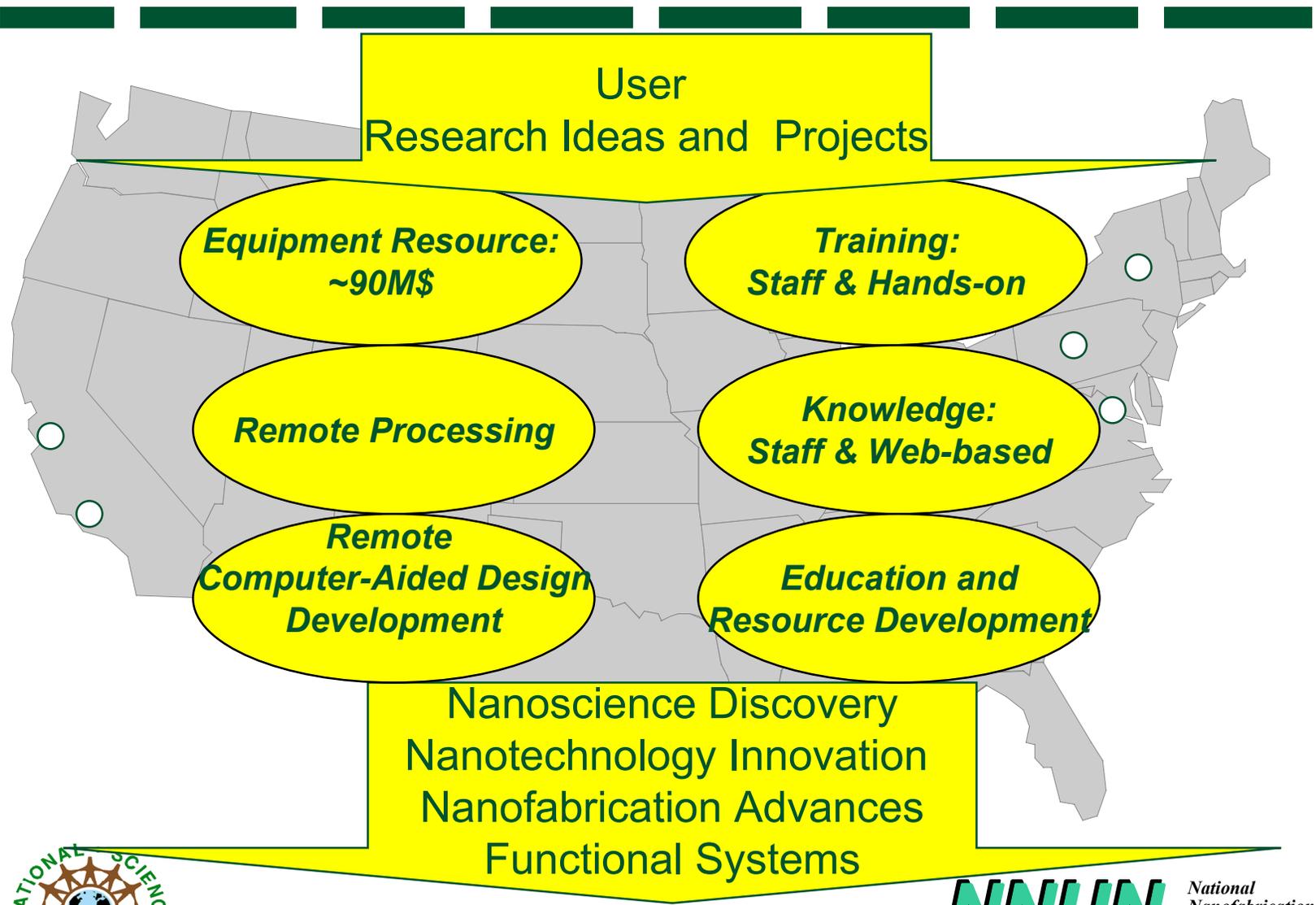
- Bridge between disciplines through technical liaison and catalysis of new developments
- Education through web, workshops, short courses, ...
- Dissemination of results and technology transfer

■ Education and Outreach

- Top quality graduate students excited by accomplishments and advanced research
- Undergraduate education through research and training locally, as well as through web-resources



NNUN Approach



NanoTechnology

Nanofabrication Processes

Nanobiology

Nano and Microelectronics

Optics and Optoelectronics

Nano and Micromechanics

Nano and Microfluidics

**Solid State Physics & Chemistry
at nano-scale**

Magnetics

Ferroelectrics

Soft-materials

Quantum Structures

Nanostructure Science

Biophysics

Chemical Sensors

Molecular Applications

Self-assembled Structures

Polymers

Materials Science

Nano-Crystals

Patterning:

Lithography

**nm: Electron Beam and
Probe-based lithography**

>150 nm: Optical

Embossing

Dry etching

Material:

Dopant diffusion

Dopant implantation

**Magnetic, ferroelectric,
dielectric, ... materials**

Polymers and resists

Structural:

Depositions

**Growth of films – hot and
other physical processes**

Contacts

Physical:

**Characterization at
nano-scale: AFM, STM,
AFM, BEEM, ...**

Optical Probing

Electronic Probing

Self-Organized/Synthesis

Block-Copolymers

Nanocrystal synthesis

Self-assembly processes



NNUN Operational Characteristics

■ Productive experimental resource for:

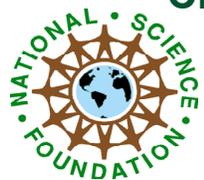
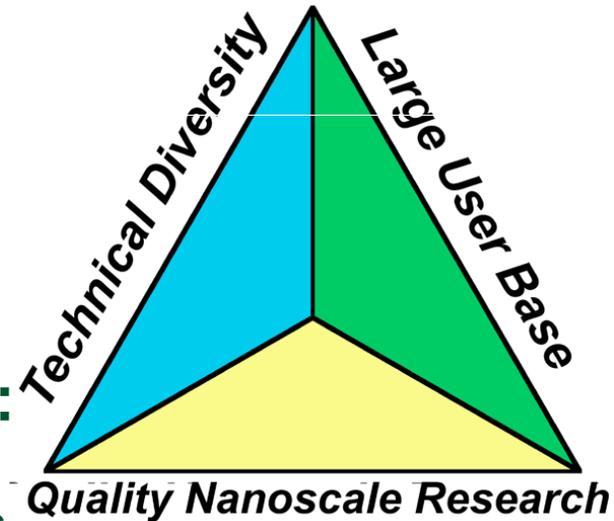
- New and traditional approaches to nanofabrication
- New applications of nanofabrication
- Leading edge technology
- Catalyst for new developments

■ Unique educational resource for:

- Training for students (graduate and undergraduate) and scientists and engineers
- Dissemination of results and transfer of technology

■ Efficient use of national resources

- Critical mass



Strength of the Network Concept

- **Networked expertise**
 - Complementary & common expensive research resource (equipment, knowledge, staff) with enhanced capability
 - Shared knowledge dissemination and outreach
- **Integrated access (<http://www.nnun.org>) with user / project coordination**
 - Critical mass of users at sites and across network
- **Shared learning – processes, facility operation, etc., and transfer of successes**
- **Enhanced visibility and interactions with community**
 - Networked Research Experience for Undergraduates
 - Workshops
- **Equipment & software compatibility (evolving) and back-up**
- **Joint resource development**



NNUN Culture

- **Fair and open access for any research project of merit to all equipment and processes**
 - Strong university support and infrastructure
 - Strong faculty and staff commitment to sharing and promoting outside usage
 - Strong internal research program for providing critical research mass and knowledge
- **State-of-the-art experimental facility with**
 - Flexibility (wafers, processes, materials)
 - New techniques
 - On-site training for users
 - Skilled support personnel to assist users



NNUN Facilities

- **State-of-the-art equipment and process expertise**
 - Physical and Chemical Techniques: Electron, optical, and mold-assisted lithography; dry and wet chemistry patterning; deposition techniques; semiconductor hot processes; surface-oriented processes; specialized processes such as wafer bonding, selective chemistries, ion-implantation, other doping techniques; characterization; etc.
- **Flexible equipment: wafers, processes, materials, etc.**
- **Acceptance of experimental risks associated with multitude of processes and materials**
- **Rapid adaptation and development of new techniques and openness to new ideas**
- **A structure that allows complexity of many processes and many tools to be coordinated for integrated success**
- **NSF provides ~36% of funds which principally support staff; user fees, etc. fund remainder**



NNUN Snapshot

- **Network activity growing extremely rapidly**
 - Number of users (~20% growth rate; doubling in 4 years)
 - In other measured parameters - fees, hours, etc.
- **New disciplines growing rapidly**
 - Healthy balance between disciplines
 - Science and engineering
 - Smaller equipment-specific projects and larger integration projects
- **Instrumental in several key research breakthroughs**
 - Strong quality of this research
- **High levels of measured user satisfaction**
 - Strong user research support
- **NNUN supported the experimental education of over 1100 graduate and undergraduate students in 2001**
 - ~ 300 PhD awards depended on NNUN resources
- **NNUN supported effort of >120 small companies during 2001**
 - ~25 companies seeded by research from NNUN



NNUN (<http://www.nnun.org>) Web Access

- Information delivery
- Entry point for all sites
- Events
- Courses
- Processes
- Research
- Training
- Equipment
- ...



Search Results

NUN

- Main Page
- NNUN Mission
- Network Partners
- Event Calendar
- Newsletters
- Biotech Program
- REU Program
- Contact NUN
- Search

Search Results

Location: [http://128.111.237.68:8080/Phantom.aog\\$search](http://128.111.237.68:8080/Phantom.aog$search)

etching

Searching for "etching" found **942** pages and returned

- [100%] [CNF PI & Users, 1/2000](#) 248.7K Ja CNF PI Users, 1/2000 CNF Principal Invest listing of all the active CNF PIs and USERs Last Name of PI or USER. PROJ LAST, P <http://www.cnf.comell.edu/cnf/projects/hu>
- [100%] [CNF PI & Users, 1/2000](#) 227.6K Ja CNF PI Users, 1/2000 CNF Principal Invest listing of all the active CNF PIs and USERs Project Number. LAST, FIRST PI's Last N <http://www.cnf.comell.edu/cnf/projects/hu>
- [18%] [SNF: Plasma Oxide Etching](#) 2.5K 1 SNF Plasma Oxide Etching SNF Process Li Pre-treatments To prevent resist burning, v hour at 110 C Oven bake. Etch process Pre Flow 85... <http://www.snf.stanford.edu/Processes/pr pages>
- [17%] [Polysilicon Plasma Etching](#) 13.2K 1 Nitride Plasma Etching The following infor determination of appropriate equipment for programs and results are given. The user ma <http://www.snf.stanford.edu/Processes/pr pages>
- [17%] [Silicon Chrome](#) 6.7K Feb 22, 2000 sichrome CHSi Silicon Chrome may go in the WITH APPROVAL ONLY see Jim McVit -- WITH APPROVAL ONLY see Jim McV

Nitride Plasma Etching

Location: <http://www.snf.stanford.edu/Processes/proclibrary/plasma/nitride.html>

The following information is provided to SNF users to aid in the determination of appropriate equipment for their etching needs. Standard or typical programs and results are given. The user may want to tailor the programs to fit their specific process. Etch rates and selectivities are given as a starting point only and should not be considered to be current. It is highly recommended that users establish the etch rates for their work by the use of test wafers as close in material and masking pattern as possible to the device wafers to be etched.

Drytek 2

Pre-treatments:

- None needed.

Etch Process (typical program):

Pressure	200 mTorr
SF6	50 sccm
CF3Br	33 sccm
RF Power	500 Watts

Post-treatments:

- None needed.

Etch Rates and selectivities:

Material	Etch Rate
Nitride	700 Å/min



Technical Education and Use

New Page 1 - Netscape

File Edit View Go Communicator Help

Back Forward Reload Home Search Netscape Print Security Shop Stop

Bookmarks Location: http://www.cnf.cornell.edu/cnfprocesses/cnf_process.htm What's Related

CNF Cornell Nanofabrication Facility **CNF PROCESS LIBRARY**

PROCESSES

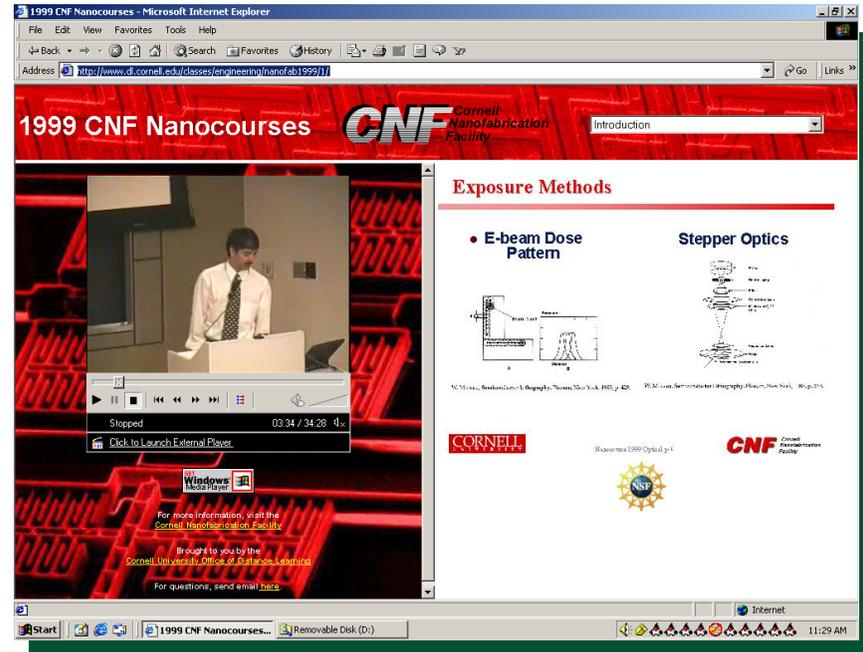
- [Clean Process capabilities](#)
- [Deposition and growth process capabilities](#)
- [Thermal process capabilities](#)
- Etch process capabilities: 1. [Dry](#); 2. [Wet](#)
- [Bonding process capabilities](#)
- Lithographic process capabilities
- Ion Implantation process capabilities
- [Chemical Mechanical Polishing process capabilities](#)

- Chemical Mechanical Polishing II
 - Process: silicon oxide planarization
 - Equipment: Strasbaugh
 - Polishing pad: Rodel IC14000
 - Slurry: Cabot SS12
 - Polishing pressure (psi): 9
 - Table speed (rpm): 35
 - Carrier speed (rpm): 15
 - Removal rate (Å/min): 3000
- Chemical Mechanical Polishing III
 - Process: Polysilicon
 - Equipment: Strasbaugh
 - Polishing pad: Rodel IC1400



Technical Outreach: Nanocourses

- **Nanofabrication technology courses for new users**
 - Lithography
 - Vacuum techniques
 - Plasma techniques
 - Thin Film techniques
 - Hot processes
 - New techniques
 - Characterization
- **Presented by staff in short course format with printed notes**
 - 24 lecture hours



Available in streaming video on web

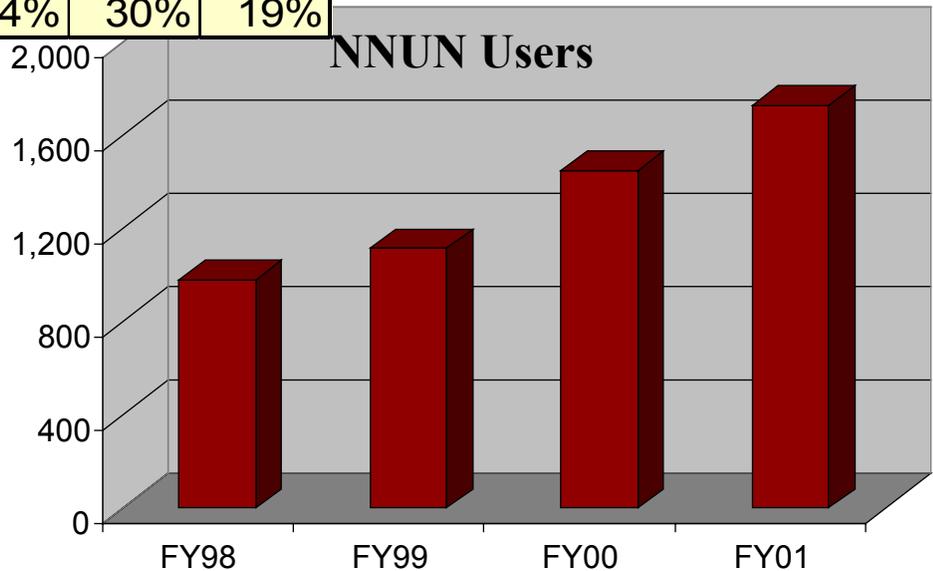
<http://www.cnf.cornell.edu/nanocourses/nanocourse.html>



NNUN Users

	FY98	FY99	FY00	FY01
NNUN Users	981	1,114	1,449	1,729
NNUN Annual User Growth Rate		14%	30%	19%

(Unique User: same individual through the year is counted as 1 user.)

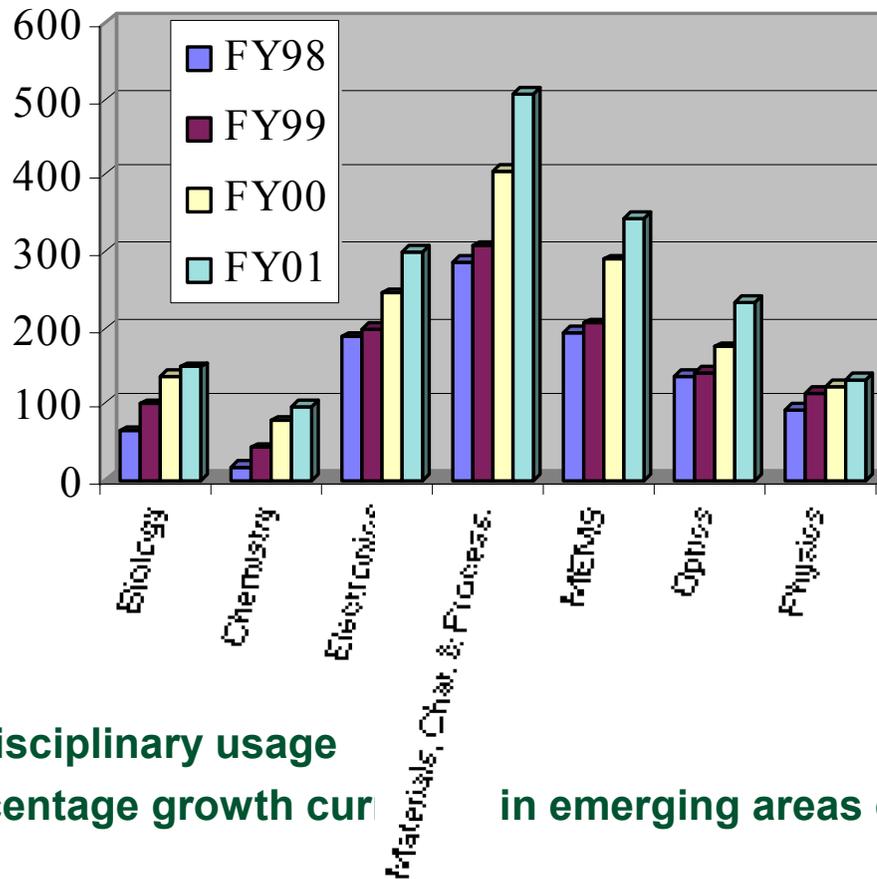


- A doubling of users in 4 years
- A similar large increase in small-company usage



NNUN User Base by Discipline

NNUN User Distribution by Field

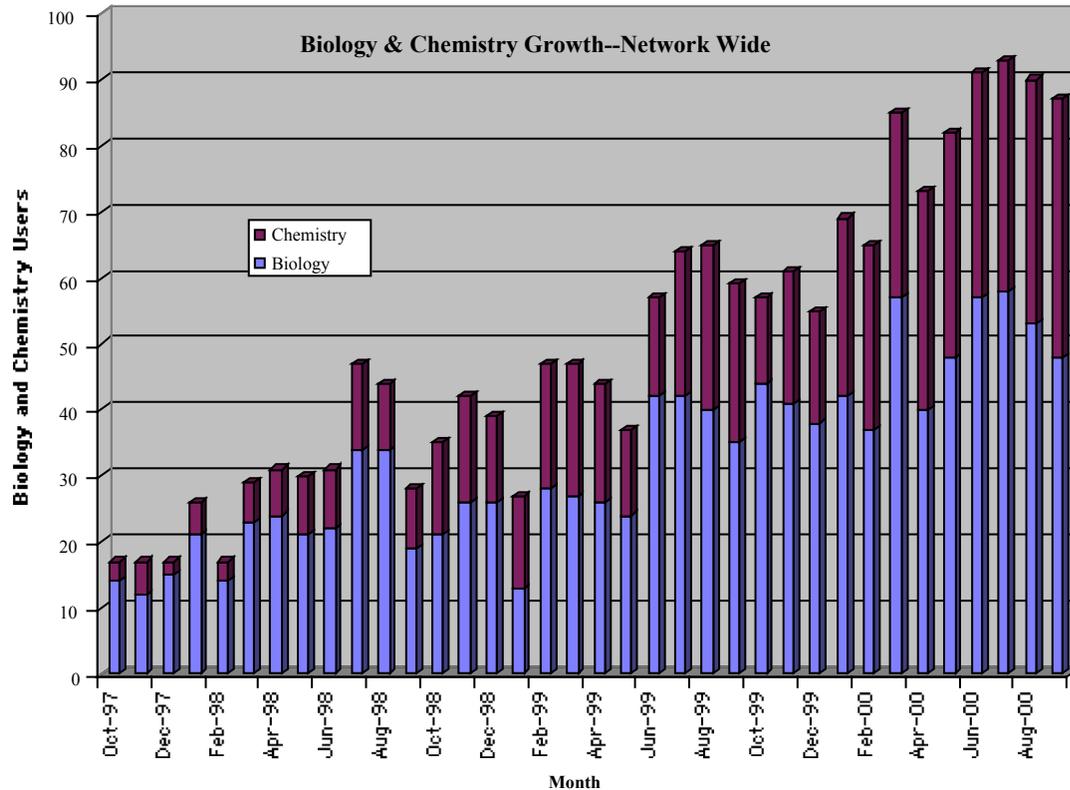


- Large interdisciplinary usage
- Largest percentage growth curve in emerging areas of biology and chemistry

in emerging areas of biology and



Trend in NNUN Biology and Chemistry Users



- Strong steady growth reflecting broad interest in biology and chemical applications
- NNUN helped through domain experts and development of capabilities



User Distribution Snap-Shot

Data by zip-code without weighting for number of users from the zip-code



- Diverse user base from across the nation reflecting the distribution of high tech industry, many of the major universities, and the distribution of NNUN sites.



How to Use NNUN

- Check <http://www.nnun.org>
- Visit and search on projects, resources, capabilities of the facilities (visit individual sites)
 - Look at projects, reports, etc. at sites
- Contact us through user program managers of the sites
 - IP is not an issue because we ask you not to tell us your confidential information, but there are few voice and e-mail technical and administrative exchanges
 - But, you need to tell us sufficient details of what you wish to accomplish
 - Establish the appropriateness of our capabilities
- Send short project description and MOU
- Start project in 2-6 weeks
- Some projects can also be accomplished remotely



NNUN Experience

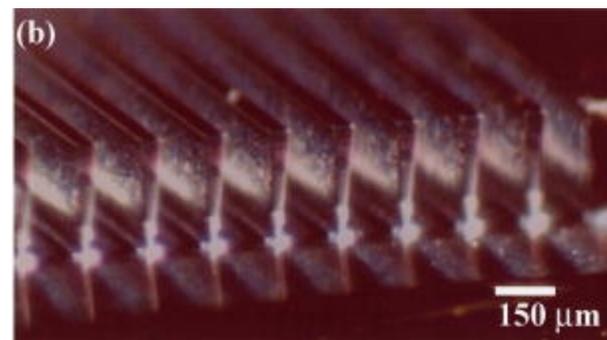
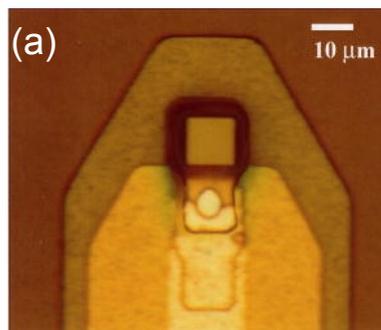
- **NNUN is a very effective use of resources and very successful in execution of nanostructures science and engineering research**
 - the variety of nano-science and -technology demands and consequent compromises make networked universities (with critical mass) as the appropriate location
- **Research in nanostructures requires coordination of multiple fabrication, synthesis, and characterization tools (typically 20-30 time-sensitive process steps, but could be as high as 200 in electronics/systems)**
 - Complexity of execution increases at a faster rate with projects
- **Requires expensive equipment (lithography tools, e.g., are \$1-5M) that require distributed networking**
 - Cost of new instrumentation has increased at a rapid pace during the past years
 - Cost of service contracts is high
 - New users at nano-dimensions => increased capital needs
- **Requires expert staff**
 - Need to be competitive with industry
 - Staff needs to be user-oriented with strong research skills



Microvolume Field-Effect pH Sensor for Scanning Probe Microscope

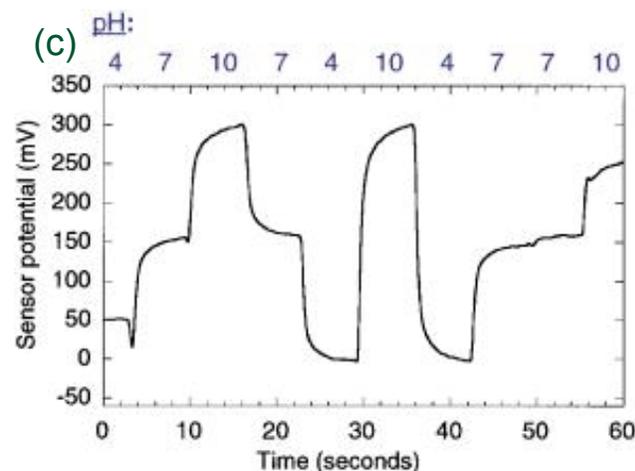
Quate et al. Stanford

The scanning probe potentiometer (SPP) is a pH-sensitive, micron-sized field-effect sensor, capable of measuring pH gradients over a surface (top view, (a)).



Multiple solutions of varying pH were introduced from microfabricated channels into a reservoir (cross-section, (b)). Because of the laminar flow conditions, the streams will not mix in the reservoir.

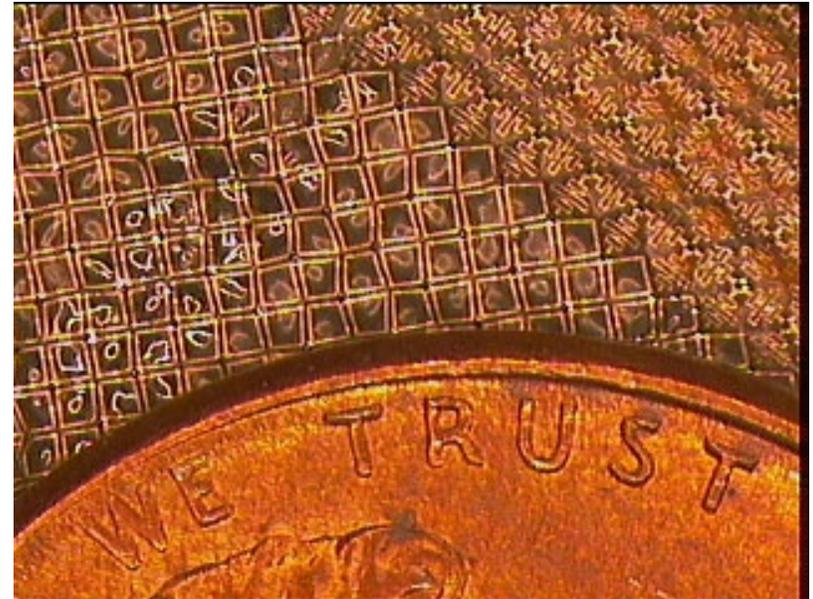
The SPP was scanned across the reservoir, successfully detecting the different pH's associated with the individual streams.



A Sensor System to Measure Contact Stress Distributions in the Human Knee

M. Hull, UC-Davis

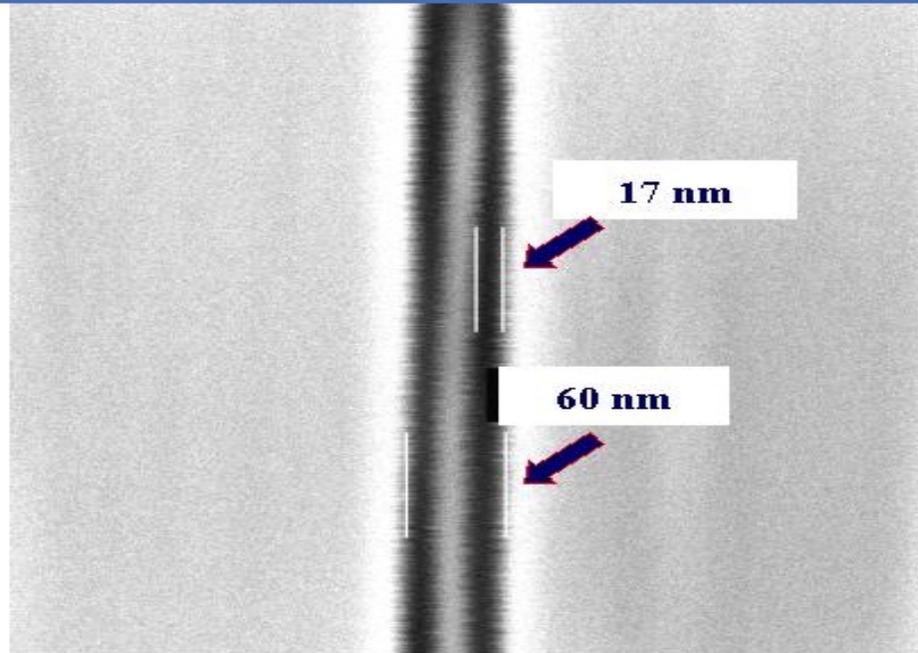
- **1500 independent sensors to measure normal stress**
- **Flexible and extensible 2-D sensor array that conform to complex knee cartilage curvatures**
- **Sensor array <70 μm thick**
- **30 x 50 mm array**
- **Novel stress sensor design and processing**



Sensor array on Silicone rubber backing is shown with a penny

Reduction of Dimensions using SAM

Molecular Ruler for Scaling Down Nanostructures Formation of Precisely Defined Electrode Spacings



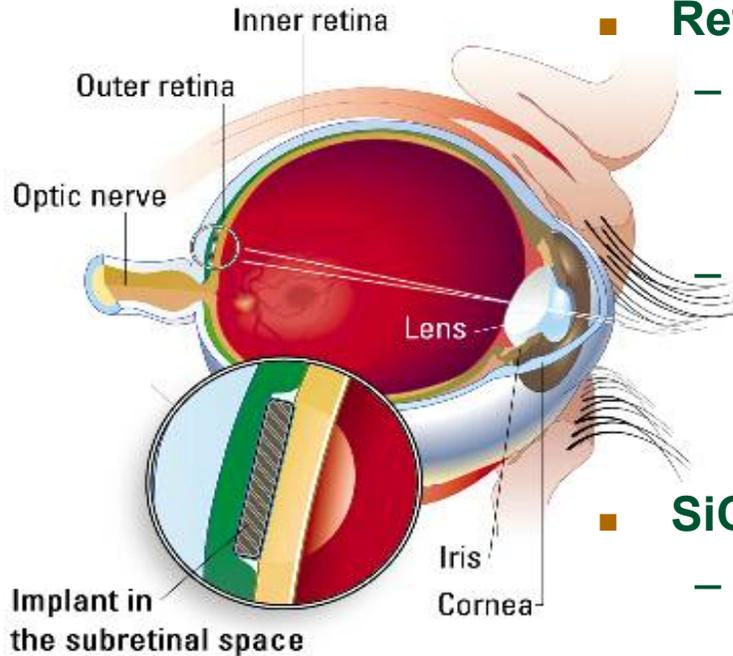
FE SEM Image of a metal wire ~17 nm wide between parent electrodes from an initial gap of 60 nm (with 20 nm ruler spacing)

A. Hatzor & P. S. Weiss, submitted to *Science*

PS Weiss



Artificial SiC Retina Chow & Chow (Optobionics)



■ Retina Disease

- AMD age-related macular degeneration-injury to the photoreceptor layer
- RP retinitis pigmentosa- injury to the photoreceptor layer usually hereditary in nature and produce “tunnel vision”

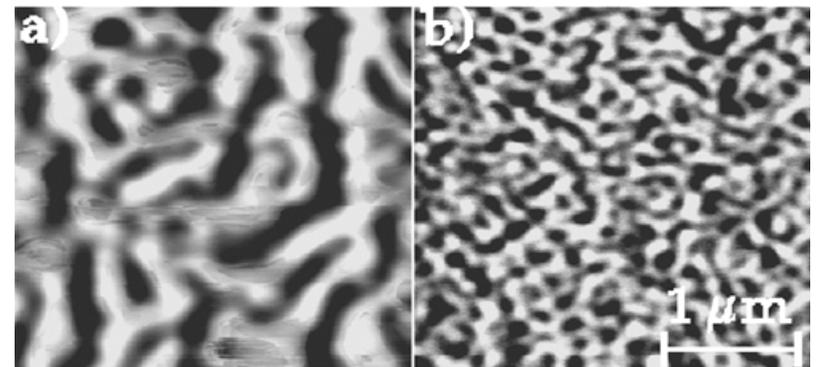
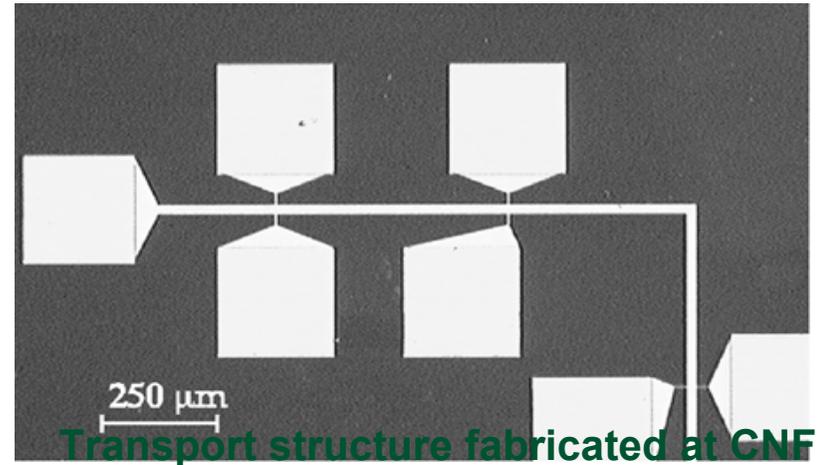
■ SiC retina

- highest sensitivity in the blue region
- compatibility
- higher output voltage
- inert

Properties of Small Scale Magnetic Structures

Jun Yu and Andy Kent, NYU

- Control of magnetic domain configurations in small structures with nanometer scale domain wall widths
- Ordered $L1_0$ Fe Pt has among the highest known magnetic anisotropy energy of any ferromagnetic material
- First evidence for intrinsic domain wall scattering contribution to resistivity in a transition metal ferromagnet.



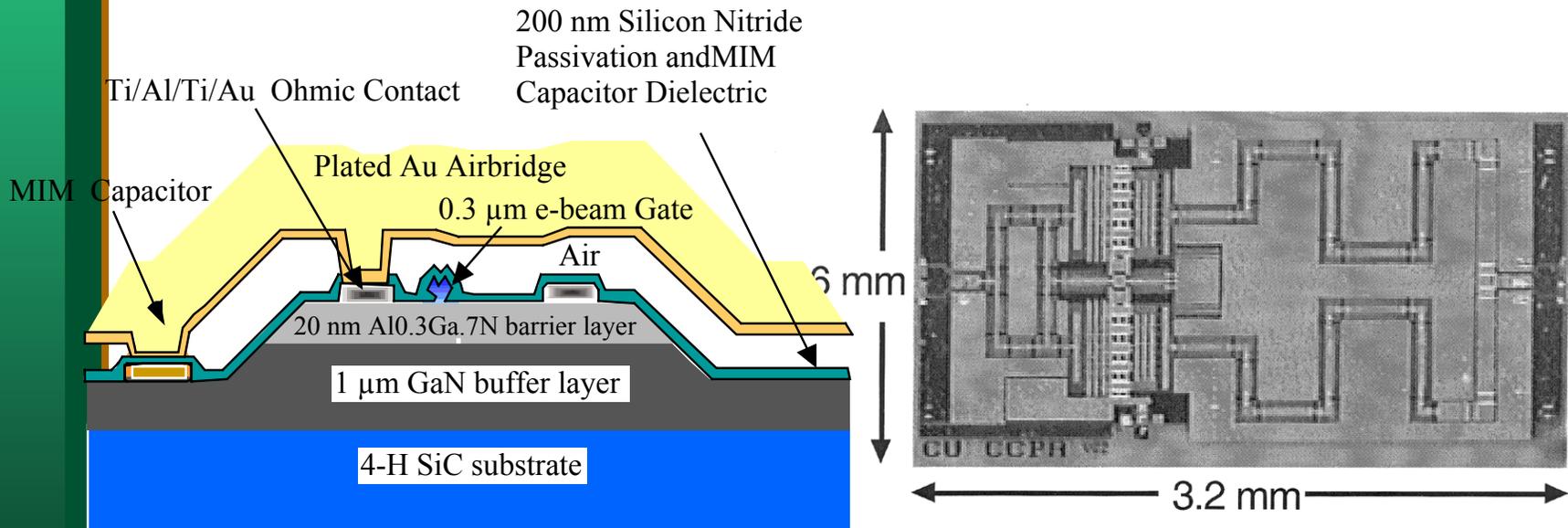
MFM images of ordered films



High Speed Large Bandgap Transistors and Circuits

L. F. Eastman et al. (Cornell)

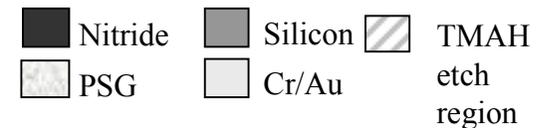
- Dopant free AlGaN/GaN HEMTs and circuits on SiC substrates with 10.7 W/mm of RF power at 10 GHz and >5W of total power



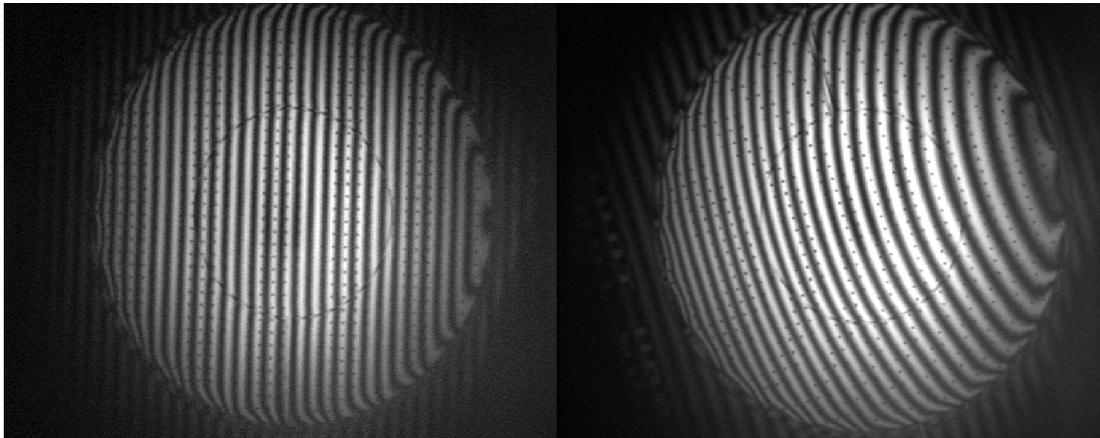
Deformable Silicon Nitride Mirrors for Focus Control

David Dickensheets (Montana State University)

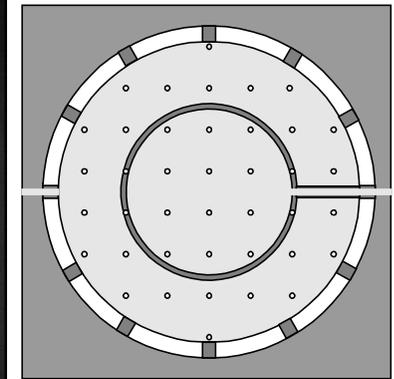
- 1mm diameter mirror with 36-360 mm focal length control at zero primary spherical aberration using deep sub-wavelength dimensions
- Active bias control



Cross Section



Interference images of 1mm mirror. a) 0 volts applied.
b) 65 volts applied to center and outer electrodes.



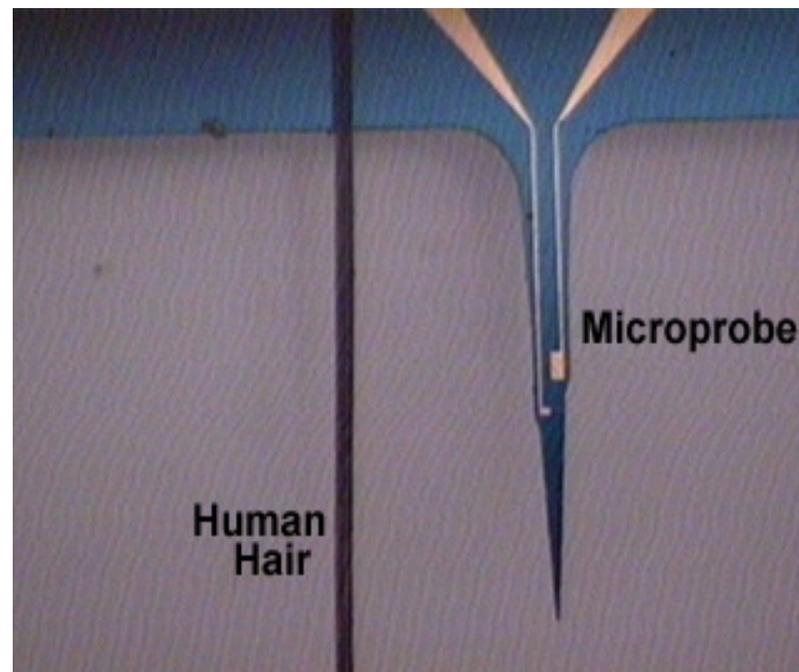
Top View



Integrated Sampling Devices for Bioanalysis

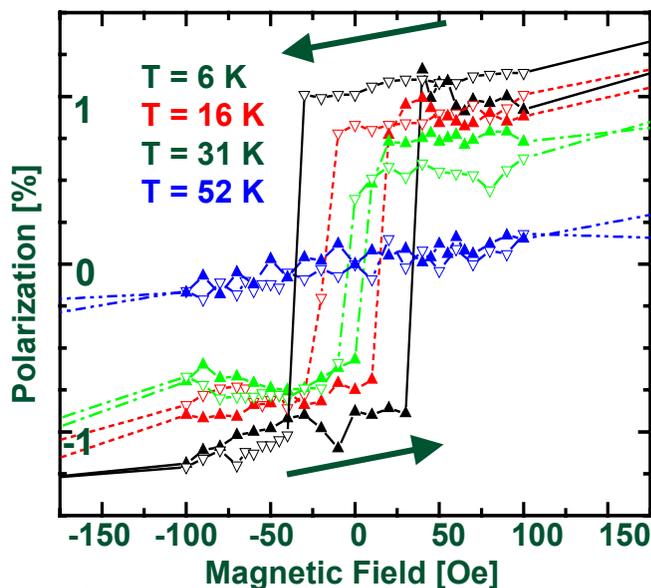
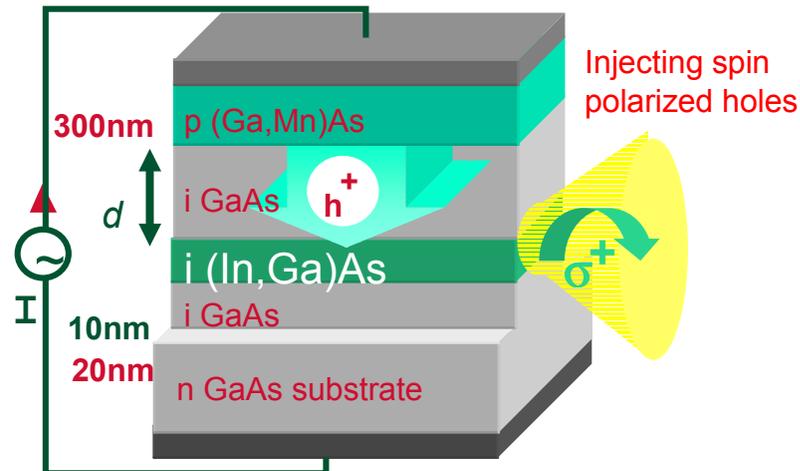
W. H. Smart (Kumetrix)

- **A Silicon Microsampling Device for bioanalysis of ultra-small dimensions.**
- **Advantages**
 - Small, flexible micro-needles and probes offer painless insertion
 - Small size allows for nonrestrictive attachment to the body for continuous monitoring of an analyte, such as lactate
 - High volume, low cost production of devices



Spin-Polarized Light Emitting Diodes

D. Awschalom (UC-Santa Barbara)



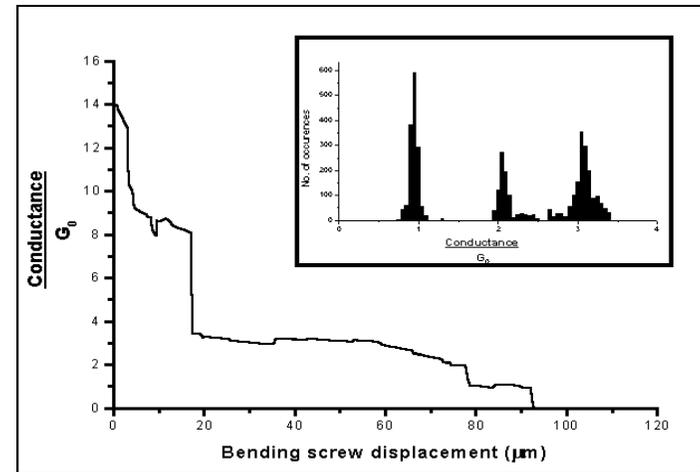
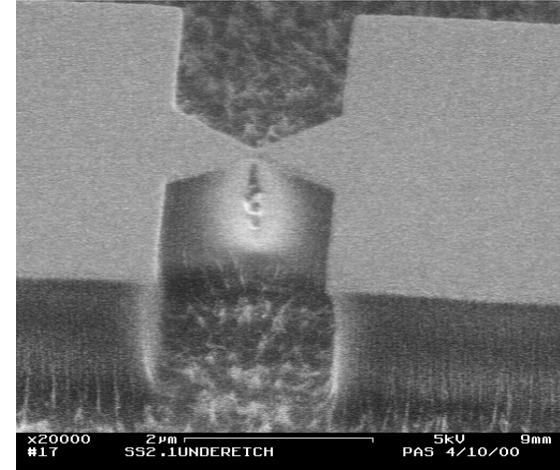
- (Ga,Mn)As - a p-type, hole-induced ferromagnetic semiconductor, readily grown on GaAs
- Spin-polarized holes injected from (Ga, Mn)As, transported > 200 nm to recombine in (In,Ga)As
- Polarization of emitted light tracks magnetization below T_c of (Ga,Mn)As



Atomic Scale Break Junctions for Molecular and Nanostructural Measurements

Dan Ralph, Cornell

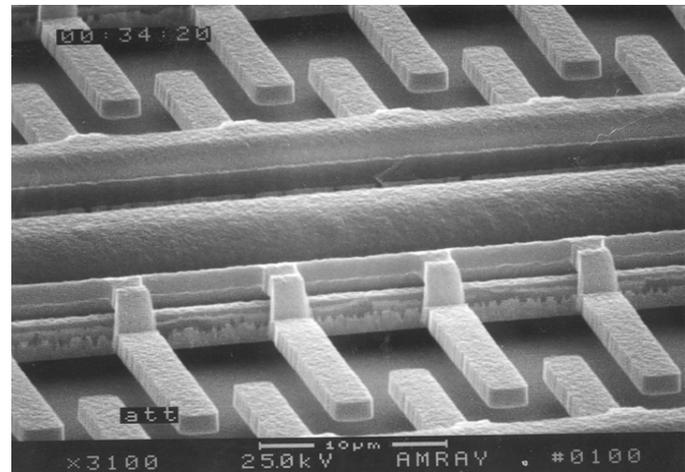
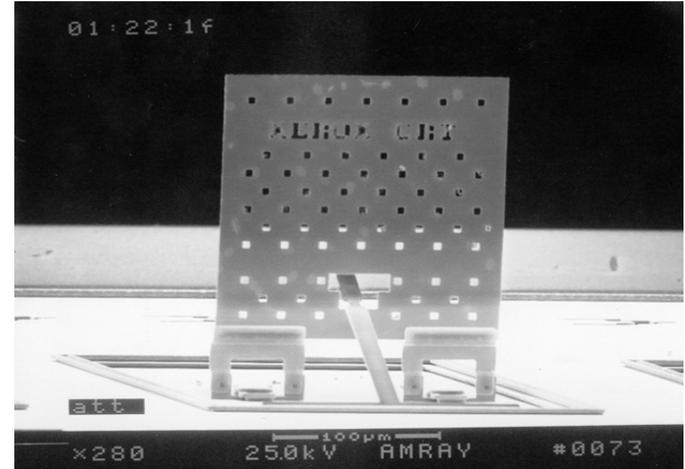
- Mechanically controllable break junctions fabricated by e-beam lithography on flexible substrates
- Conductance quantization can be observed at low temperature as the wire is stretched to atomic dimensions
- Used for measurements of properties of magnetic tunneling devices and transport characteristics of single molecules and small nanostructures



MEMS technology for Advanced Imaging Systems

Alex Tran, Xerox

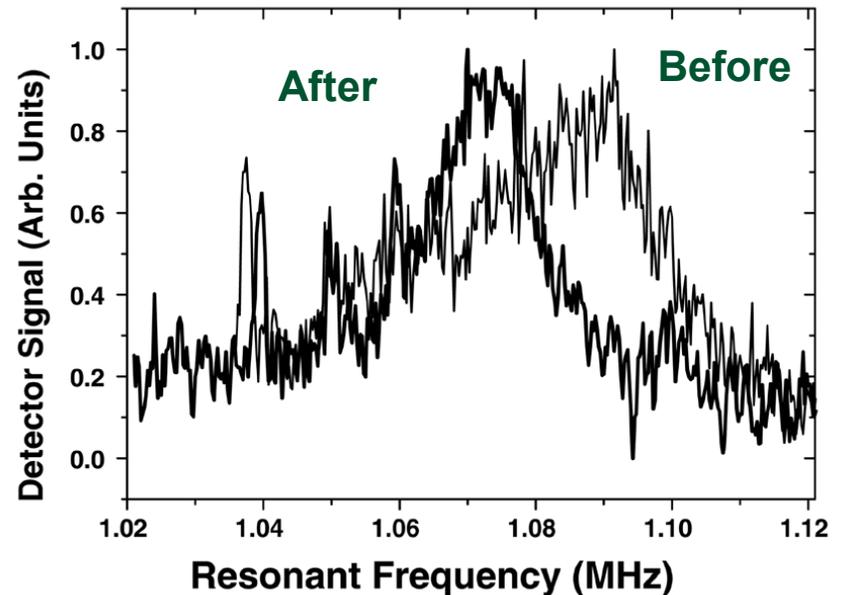
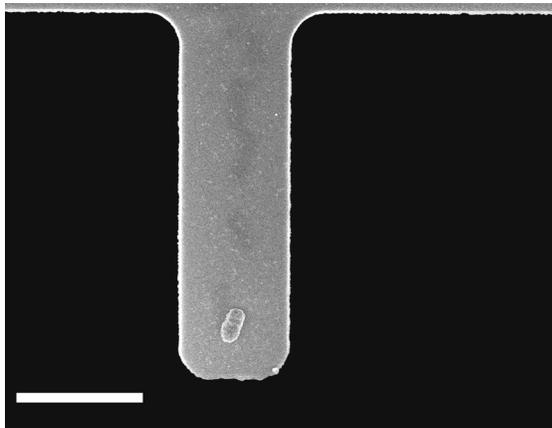
- **3 level poly-silicon on SOI MEMS process for optical and microactuators**
- **High quality optical components together with micro-dimensional MEMS components**
- **Polysilicon provides mechanical elements only**
- **Applications to optical imaging and optical communications**



Single Cell Detection using Mechanical Oscillations

H. Craighead (Cornell)

- Highly sensitive resonant sensing using nano-mechanical silicon nitride cantilever beams.
- Detects specific binding of E. Coli antibody monolayers

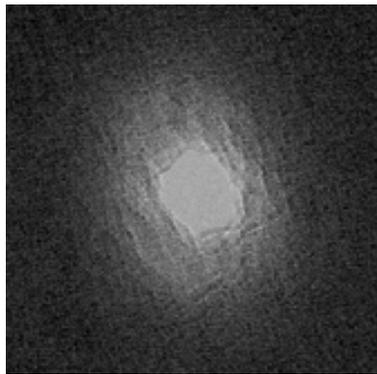


Nano-Magnetics: Spin-Torque Effects

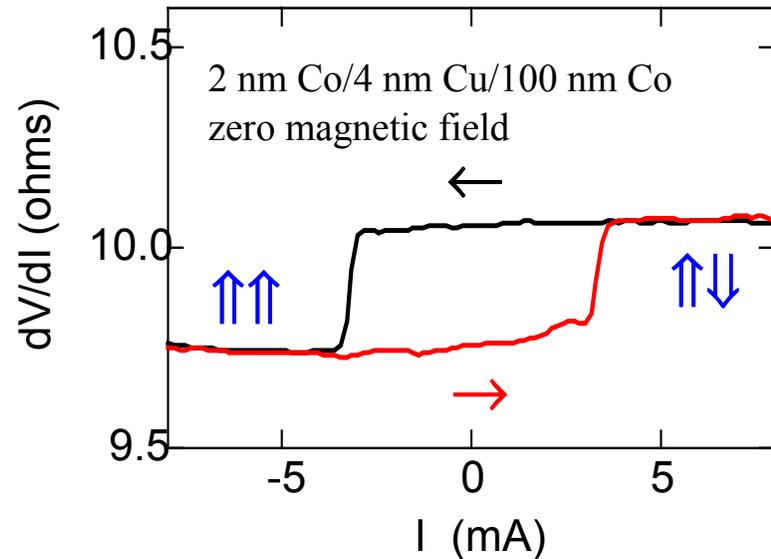
D. Ralph et al., Cornell

Demonstration of torque by spin-polarized current causing single-domain switching

- measured in nanostructures



30 nm



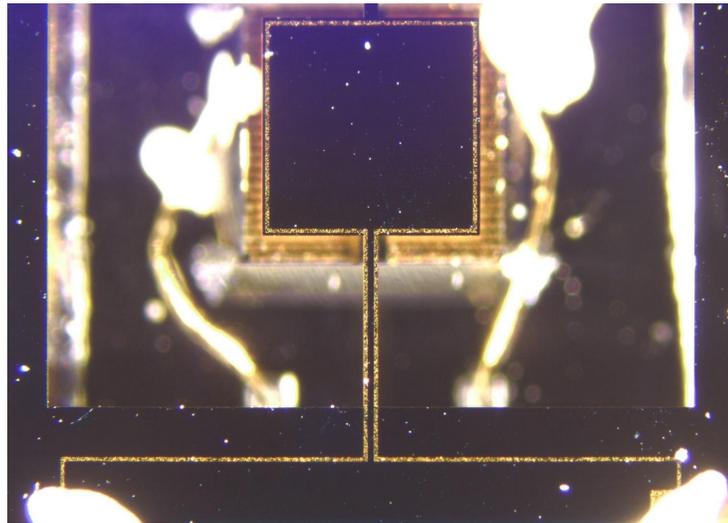
Ralph et al.



Torsional Magnetometer

M. J. Naughton (Boston College)

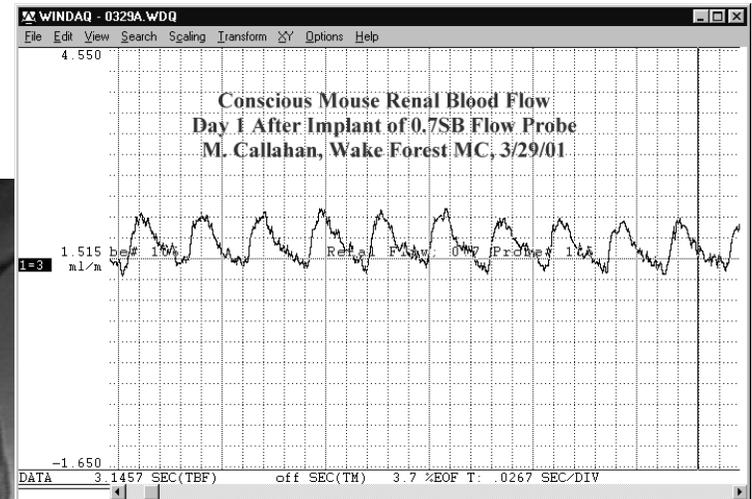
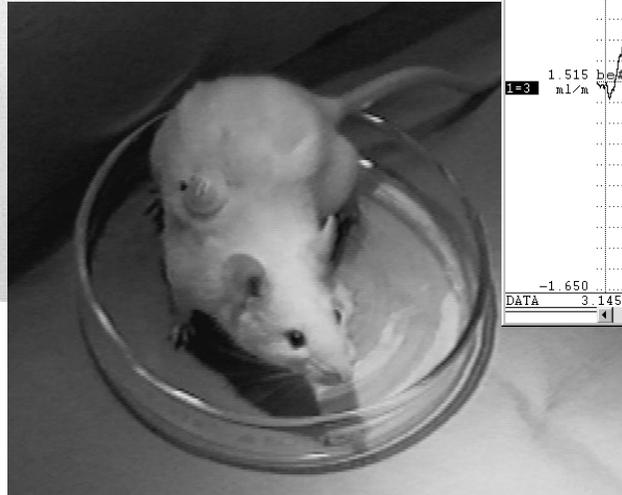
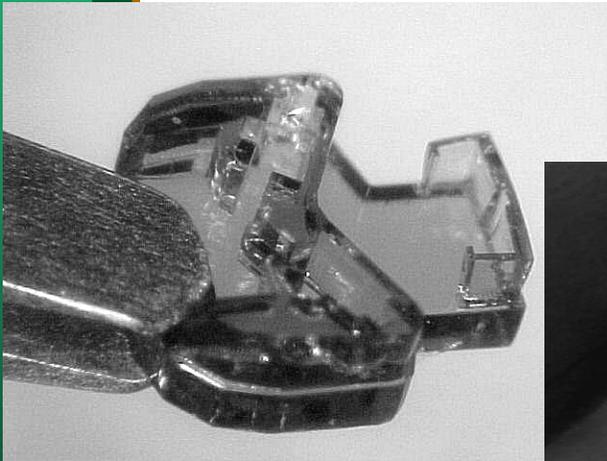
- High sensitivity magnetometer using small metal loops, with isotropic torque rejection, for measurement of uniform magnetic fields.



Micro-Machined Flow Probe

C. J. Drost et al. (Transonic Systems)

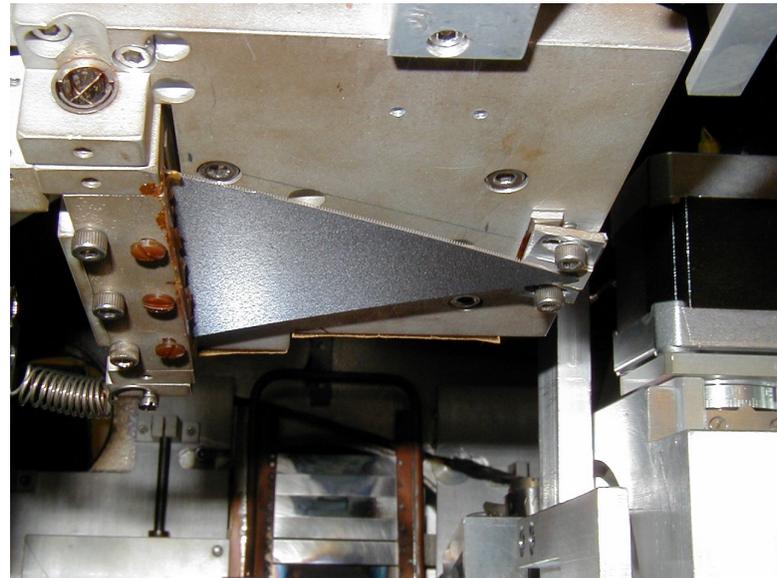
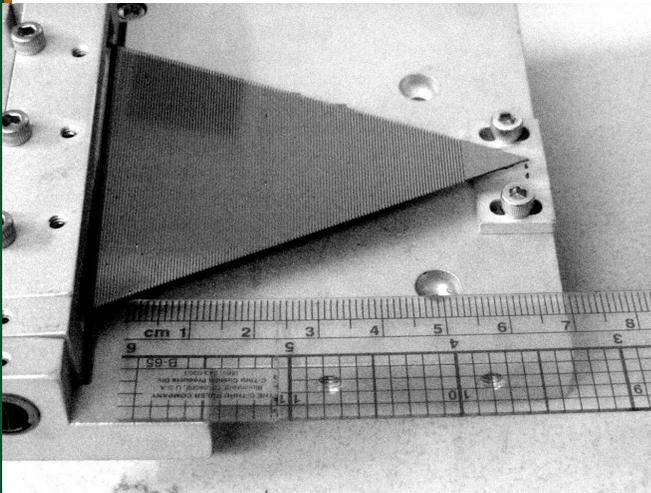
- Miniature blood flow monitoring system using photoepoxy based two-layer probe.
- Smallest transit time flow probe
- Used to monitor arterial blood flow into kidney



Micro-Fabricated X-Ray Optics

K. Finkelstein et al. (Cornell)

- Use of deep (650 um) trenches and rib structure in X-ray lenses.
- Achieved 1.3×10^{12} photons/second at 9KeV into a $1 \times 1 \text{ mm}^2$ spot without compromising energy resolution.

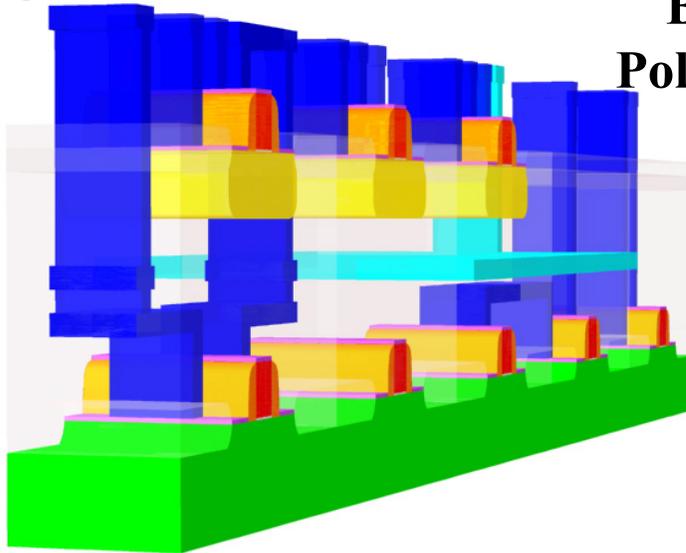


Silicon 3D Electronic Integration

L. Xue, C. Liu and S. Tiwari, Cornell

New low temperature single-crystal silicon layering technique

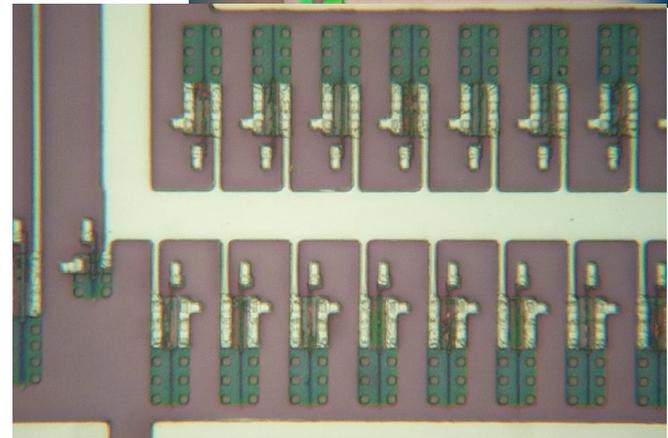
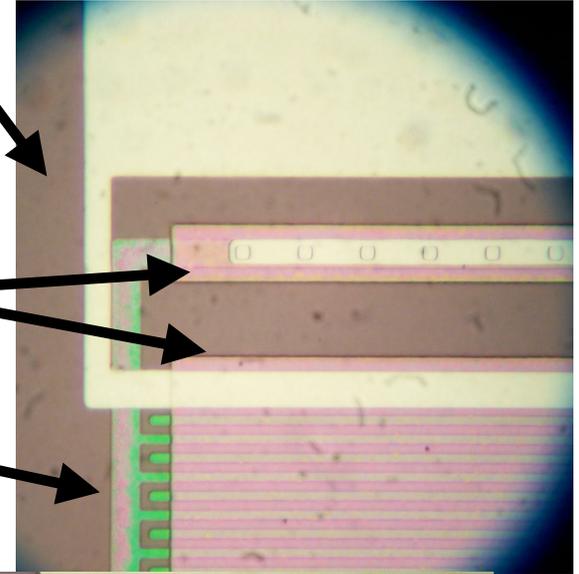
First demonstration of low temperature multi-layer electronics



LOCOS in top silicon layer

Top single-crystal silicon layer

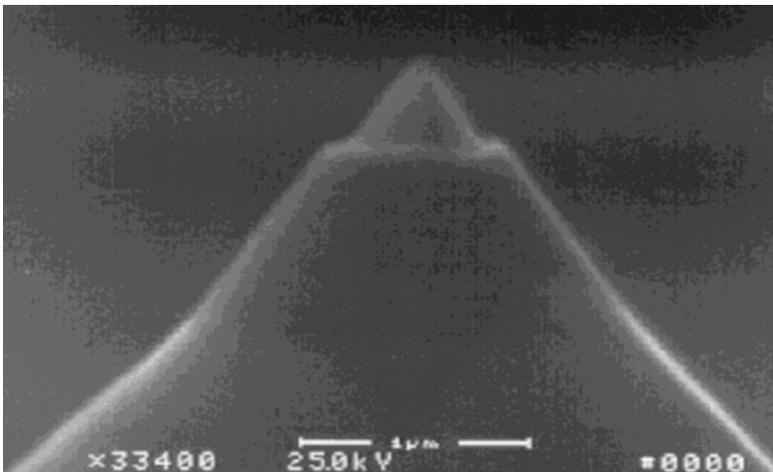
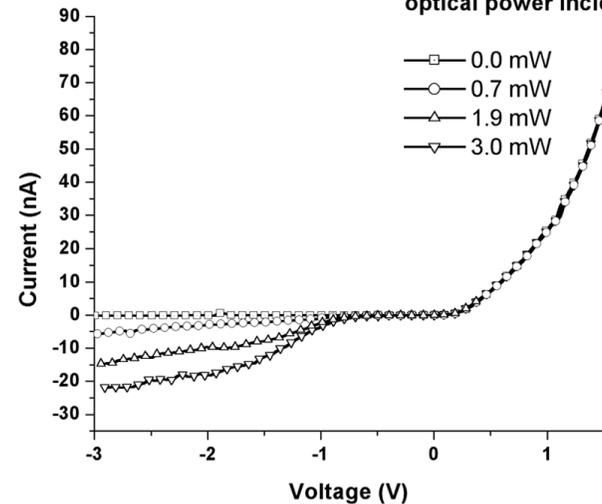
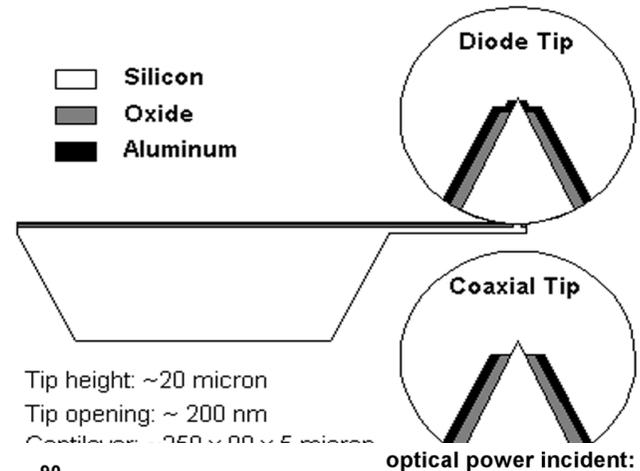
Buried Poly-Silicon



Multifunctional Scanning Force Microscope Tips

Andreas Koglin, Bjoern Rosner, Dan van der Weide, U. Wisconsin

- Schottky diode tips for photon and thermal detection
- Coaxial tips for high frequency probing of electric fields



Photodiode tip

Photodiode tip

NNUN

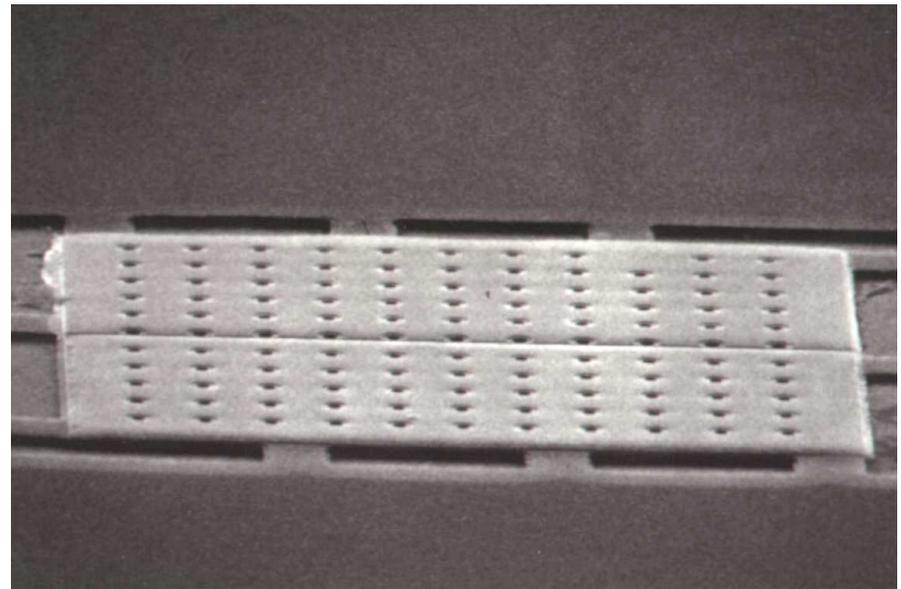
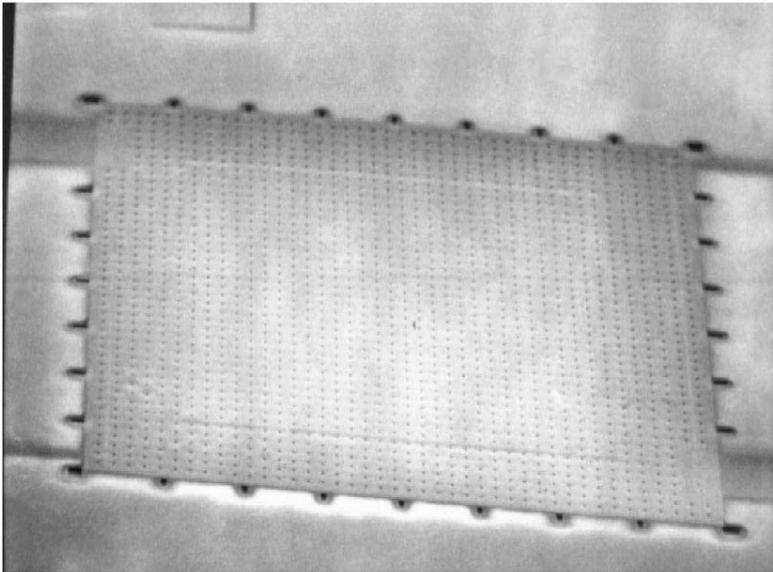
National
Nanofabrication
Users Network



Broadband 0.3 μm to 100 μm Uncooled Bolometer

D. P. Butler et al. (SMU)

- **Y-Ba-Cu-O based uncooled IR detector with a broad spectral response**



Carbon based Nanostructures

Guillorn & Simpson (U. Tenn.)

- Reproducible field emission from nanotubes and fibers

